

IN THE ABSTRACT

Please amend the Abstract of the Disclosure as shown below. A clean copy of the Abstract of the Disclosure is attached hereto.

ABSTRACT

~~The invention relates to a~~ A maskless lithography system for transferring a pattern onto the surface of a target. ~~target, comprising at~~ At least one beam generator ~~for generating~~ generates a plurality of beamlets. ~~beamlets, modulation means comprising a~~ A plurality of modulators ~~for modulating~~ modulate the magnitude of a beamlet, and a control unit ~~for controlling~~ controls each of the modulators, ~~wherein the~~ modulators. The control unit generates and delivers pattern data to ~~said modulation means~~ the modulators for controlling the magnitude of each individual ~~beamlet, the~~ beamlet. The control unit ~~comprising~~ includes at least one data storage for storing the pattern data, at least one readout unit for reading out the data from the data storage, at least one data converter for converting the data that is read out from the data storage into at least one modulated light beam, and at least one optical transmitter for transmitting ~~said the~~ at least one modulated light beam to ~~said the modulation means~~ modulators.